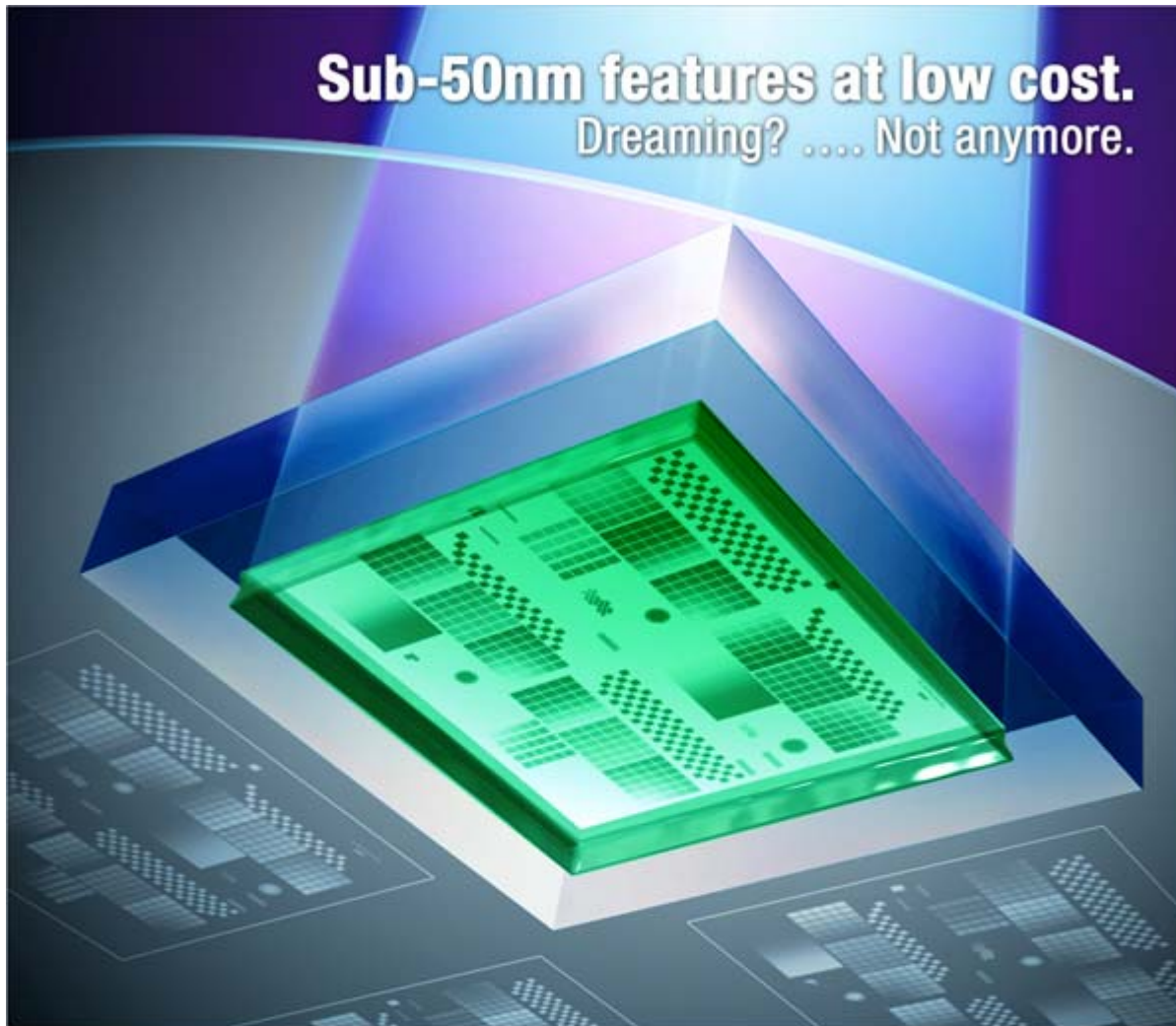


See Molecular Imprints' latest ad in the following magazines for 2004:

Compound Semi
Microlithography World
Small Times Magazine



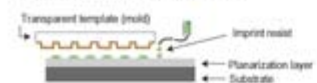
Economical, effortless nano-fabrication.

A new, revolutionary way of imprinting has arrived. You can now create multi-layer, nano-scale structures at the resolution of e-beam lithography without the throughput limitations.

Molecular Imprints has commercialized a new and unique Step and Flash Imprint Lithography (S-FIL™) technology. This simple step and repeat, room temperature, low pressure, nano-imprint process has demonstrated patterning at sub-50nm.

The Step and Flash Imprint Lithography process:

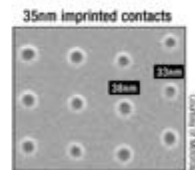
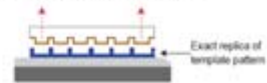
Step 1: Dispense drops of liquid imprint resist



Step 2: Lower template, fill pattern, and polymerize imprint fluid with UV exposure



Step 3: Separate template from substrate



To learn more, contact **Molecular Imprints**.

www.molecularimprints.com/ad or call 1-512-339-7760
questions@molecularimprints.com

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